

Title (en)

Hard coating layer and method for forming the same

Title (de)

Hartbeschichtung und Verfahren zu ihrer Bildung

Title (fr)

Couche de revêtement dur et son procédé de fabrication

Publication

**EP 2610364 B1 20210721 (EN)**

Application

**EP 12165051 A 20120420**

Priority

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Abstract (en)

[origin: EP2610364A1] The present invention relates to hard coating layer and a method for forming the hard coating layer. A method for forming hard coating layer which comprises: washing a substrate; installing the washed substrate in a vacuum equipment, and vacuating the chamber of the vacuum equipment; cleaning the substrate; forming oblique coating layer on the substrate; and forming vertical coating layer, vertically to the substrate, on the oblique coating layer by applying bias-voltage after forming oblique coating layer is provided. According to present invention, hardness of coating layer may be enhanced by forming a oblique coating layer and vertical coating layer on a substrate.

IPC 8 full level

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Citation (examination)

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